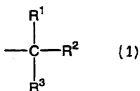


Abstract

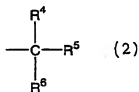
The present invention relates to a positive-working radiation-sensitive composition which is characterized in that it contains a compound meeting any of conditions a1) to a3), and b) an acid generator which generates acid by irradiation with radiation; and also to a method for the production of a resist pattern employing same.

- 10 a1) A compound wherein a carboxyl group is protected by an acid labile group represented by general formula (1)



- 15 (R¹ and R² are aromatic rings, and R³ represents an alkyl group, a substituted alkyl group, a cycloalkyl group or an aromatic ring. R¹ to R³ may be the same or different.)

a2) A compound in which an alkali-soluble group is protected by an acid labile group represented by general formula (2)



- 20 (R⁴ to R⁶ are each an alkyl group, a substituted alkyl group, a cycloalkyl group or an aromatic ring, and at least one of R⁴ to R⁶ is an aromatic ring with an electron-donating group. R⁴ to R⁶ may be the same or different.)

- 25 a3) A compound in which an alkali-soluble group is protected by an acid labile group a, and either acid labile group a has